

LINEAR SYSTEMS

Twenty-Five Years Of Quality Through Innovation

FEATURES

LOW DRIFT	$ \Delta V_{GS1-2}/\Delta T = 5 \mu V/^\circ C$ max.
LOW LEAKAGE	$I_G = 20 \text{ pA}$ TYP.
LOW NOISE	$e_n = 10 \text{ nV}/\sqrt{\text{Hz}}$ TYP.

ABSOLUTE MAXIMUM RATINGS¹

@ 25 °C (unless otherwise noted)

Maximum Temperatures

Storage Temperature	-55 to +150°C
Operating Junction Temperature	-55 to +150°C

Maximum Voltage and Current for Each Transistor¹

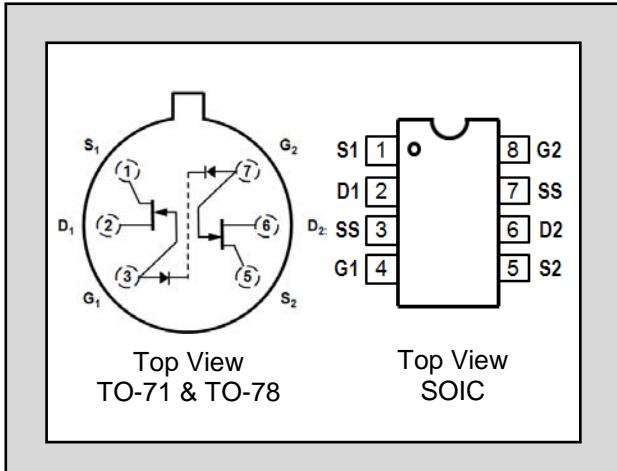
-V _{GSS}	Gate Voltage to Drain or Source	60V
-I _{G(f)}	Gate Forward Current	50mV

Maximum Power Dissipation

Device Dissipation @ Free Air - Total	400mW @ 25°C ²
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LS3954A LS3954 LS3955 LS3956 LS3958

LOW NOISE LOW DRIFT
MONOLITHIC DUAL N-CHANNEL
JFET AMPLIFIER

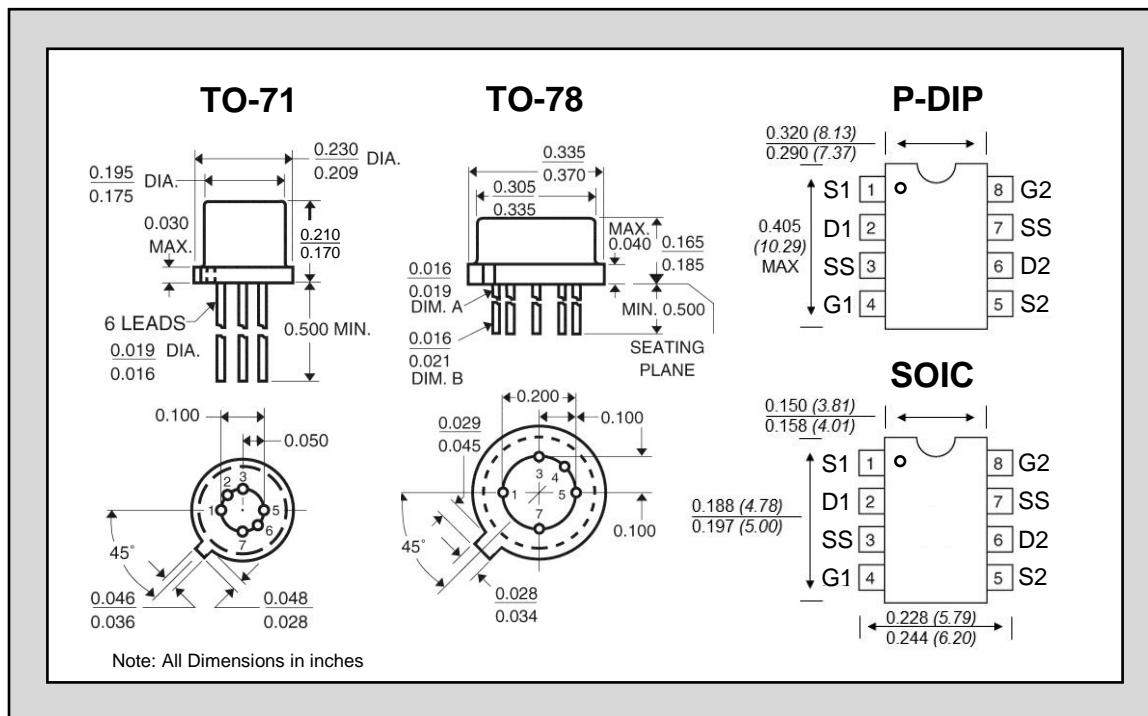


ELECTRICAL CHARACTERISTICS @ 25°C (unless otherwise noted)

SYMBOL	CHARACTERISTIC	LS3954A	LS3954	LS3955	LS3956	LS3958	UNITS	CONDITIONS
$ \Delta V_{GS1-2}/\Delta T $ max.	Drift vs. Temperature	5	10	25	50	100	$\mu V/^\circ C$	$V_{DG} = 20V, I_D = 200\mu A$ $T_A = -55^\circ C$ to $+125^\circ C$
$ V_{GS1-2} $ max.	Offset Voltage	5	5	10	15	25	mV	$V_{DG} = 20V, I_D = 200\mu A$

SYMBOL	CHARACTERISTIC	MIN.	TYP.	MAX.	UNITS	CONDITIONS	
BV _{GSS}	Breakdown Voltage	60	--	--	V	$V_{DS} = 0$	$I_G = 1\mu A$
BV _{GGO}	Gate-to-Gate Breakdown	60	--	--	V	$I_{GG} = \pm 1\mu A$	$I_D = 0$ $I_S = 0$
<u>TRANSCONDUCTANCE</u>							
g _{fs}	Full Conduction	1000	2000	4000	μS	$V_{DG} = 20V$	$V_{GS} = 0$ $f = 1kHz$
g _t	Typical Operation	500	700	1250	μS	$V_{DG} = 20V$	$I_D = 200\mu A$
$ g_{fs1-2}/g_t $	Differential	--	± 0.6	± 3	%		
<u>DRAIN CURRENT</u>							
I _{DSS}	Full Conduction	0.5	2	5	mA	$V_{DS} = 20V$	$V_{GS} = 0$
$ I_{DSS1-2}/I_{DSS} $	Differential	--	± 1	± 5	%		
<u>GATE VOLTAGE</u>							
V _{GS(off)}	Pinchoff Voltage	-1	-2	-4.5	V	$V_{DS} = 20V$	$I_D = 1nA$
V _{GS}	Operating Range	-0.5	--	-4	V	$V_{DS} = 20V$	$I_D = 200\mu A$
<u>GATE CURRENT</u>							
-I _G	Operating	--	20	50	pA	$V_{DG} = 20V$	$I_D = 200\mu A$
-I _G	High Temperature	--	--	50	nA	$V_{DG} = 20V$	$I_D = 200\mu A$ $T_A = +125^\circ C$
-I _G	Reduced V _{DG}	--	5	--	pA	$V_{DG} = 10V$	$I_D = 200\mu A$
-I _{GSS}	At Full Conduction	--	--	100	pA	$V_{DG} = 20V$	$V_{DS} = 0$

SYMBOL	CHARACTERISTIC	MIN.	TYP.	MAX.	UNITS	CONDITIONS
	OUTPUT CONDUCTANCE					
g_{oss}	Full Conduction	--	--	35	μS	$V_{DG}= 20\text{V}$ $V_{GS}= 0$
g_{os}	Operating	--	0.5	1	μS	$V_{DG}= 20\text{V}$ $I_D= 200\mu\text{A}$
$ g_{os1-2} $	Differential	--	0.05		μS	
	COMMON MODE REJECTION					
CMRR	$-20 \log \Delta V_{GS1-2}/\Delta V_{DS} $	--	100	--	dB	$\Delta V_{DS}= 10$ to 20V $I_D= 200\mu\text{A}$
CMRR	$-20 \log \Delta V_{GS1-2}/\Delta V_{DS} $	--	75	--	dB	$\Delta V_{DS}= 5$ to 10V $I_D= 200\mu\text{A}$
	NOISE					
NF	Figure	--	--	0.5	dB	$V_{DS}= 20\text{V}$ $V_{GS}= 0$ $R_G= 10\text{M}\Omega$ $f= 100\text{Hz}$ $NBW= 6\text{Hz}$
e_n	Voltage	--	--	15	nV/ $\sqrt{\text{Hz}}$	$V_{DS}= 20\text{V}$ $I_D= 200\mu\text{A}$ $f= 10\text{Hz}$ $NBW= 1\text{Hz}$
	CAPACITANCE					
C_{ISS}	Input	--	--	6	pF	$V_{DS}= 20\text{V}$ $V_{GS}= 0$ $f= 1\text{MHz}$
C_{RSS}	Reverse Transfer	--	--	2	pF	
C_{DD}	Drain-to-Drain	--	0.1	--	pF	$V_{DG}= 20\text{V}$ $I_D= 200\mu\text{A}$



NOTES:

- These ratings are limiting values above which the serviceability of any semiconductor may be impaired.
- Derate 4mW/ $^{\circ}\text{C}$ above 25°C

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